Kossel diffraction observed with X-ray color camera during PIXE of nano-scale periodic multilayer
Meiyi Wu, Karine Le Guen, Jean-Michel André, Philippe Jonnard, Ian Vickridge, Didier Schmaus, Emrick Briand, Philippe Walter, Qiushi Huang, Zhanshan Wang

To cite this version:
Meiyi Wu, Karine Le Guen, Jean-Michel André, Philippe Jonnard, Ian Vickridge, et al.. Kossel diffraction observed with X-ray color camera during PIXE of nano-scale periodic multilayer. Nuclear Instruments and Methods in Physics Research Section B: Beam Interactions with Materials and Atoms, Elsevier, 2019, 450, pp.252-256. 10.1016/j.nimb.2018.08.008. hal-02162011

HAL Id: hal-02162011
https://hal.sorbonne-universite.fr/hal-02162011
Submitted on 21 Jun 2019

HAL is a multi-disciplinary open access archive for the deposit and dissemination of scientific research documents, whether they are published or not. The documents may come from teaching and research institutions in France or abroad, or from public or private research centers.

L’archive ouverte pluridisciplinaire HAL, est destinée au dépôt et à la diffusion de documents scientifiques de niveau recherche, publiés ou non, émanant des établissements d’enseignement et de recherche français ou étrangers, des laboratoires publics ou privés.
Kossel diffraction observed with X-ray color camera during PIXE of nano-scale periodic multilayer

Meiyi Wu1,2, Karine Le Guen1,2, Jean-Michel André1,2, Philippe Jonnard1,2, Ian Vickridge3,4, Didier Schmaus3,4, Emrick Briand3,4, Philippe Walter5,6, Qiushi Huang7, Zhanshan Wang7

1 Sorbonne Universités, UPMC Univ Paris 06, Laboratoire de Chimie Physique - Matière et Rayonnement, boîte courrier 1140, 4 Place Jussieu, F-75252 Paris cedex 05, France
2 CNRS UMR 7614, Laboratoire de Chimie Physique - Matière et Rayonnement, boîte courrier 1140, 4 Place Jussieu, F-75252 Paris cedex 05, France.
3 Sorbonne Universités, UPMC Univ Paris 06, Institut des NanoSciences de Paris, 4 place Jussieu, boîte courrier 840, F-75252 Paris cedex 05, France
4 CNRS UMR 7588, Institut des NanoSciences de Paris, 4 place Jussieu, boîte courrier 840, F-75252 Paris cedex 05, France
5 Sorbonne Universités, UPMC Univ Paris 06, Laboratoire d’Archéologie Moléculaire et Structurale, 4 place Jussieu, 75005 Paris, France
6 CNRS, UMR 8220, Laboratoire d’Archéologie Moléculaire et Structurale, 4 place Jussieu, 75005 Paris, France
7 Key Laboratory of Advanced Micro-Structured Materials, Institute of Precision Optical Engineering, School of Physics Science and Engineering, Tongji University, Shanghai 200092, China

Key words: PIXE, periodic multilayer, Kossel diffraction.

Abstract

By combining Kossel diffraction with particle induced X-ray emission, we have developed a new methodology to analyze nano-scale thin films. We report the Kossel diffraction generated by irradiating Pd/Y based nano-scale periodic multilayers with 2 MeV protons. The intensity of characteristic Pd Lα X-ray emission is measured as a function of the detection angle (grazing exit). An oscillation of its intensity is observed when the detection angle varies around the Bragg angle, which corresponds to the energy of the emission and the period of the multilayer. Use of the X-ray color camera enables the whole setup to be fixed so that no angular scan is required, greatly simplifying the experimental condition. From the features of the Kossel curves, we are able to deduce that nitrided Pd/Y multilayers exhibit much less layer intermixing than the non-nitrided multilayers. The experimental results show that it is possible to distinguish by the shape of Kossel curves of multilayers with B4C barrier layers located in different interfaces. This demonstrates that Kossel diffraction is structural sensitive.

Introduction

The Kossel process refers to the interference of characteristic X-rays generated within and scattered by the atoms present within a periodic micro-structure. Typical diffraction patterns are formed around the Bragg angle corresponding to the wavelength (or energy) of the emission and the period of the lattice. In 1935, Walther Kossel experimentally demonstrated such interferences for a crystalline structure [1]. The phenomenon was then named after him as “Kossel effect”. Its observation requires two essential factors: first, the ionization of a core level in order to produce the characteristic emission; second, a periodic structure to diffract the emitted X-ray. The source for the ionization can
vary. It can be X-ray provided either by an X-ray tube [2-4] or by synchrotron radiation [5-8], energetic electrons [9-12] or energetic charged particles (protons or ions) [13-19] as we report in this paper.

Studies of both crystals and interferential multilayers using various techniques have been widely reported, but it was not until our previous paper [20] that the study of periodic multilayer by Kossel diffraction of X-rays generated by proton beam was first reported. We successfully observed the Kossel curves of Cr Kα and Sc Kα emissions of a Cr/B4C/Sc periodic multilayer irradiated by 2 MeV protons. However due to the very small solid angle of the highly collimated detector the counting statistics were not ideal even for long acquisition times, and we mentioned in our conclusion that it might be improved by using an X-ray color camera, that is a CCD camera in which each pixel can provide an energy-dispersed X-ray emission spectrum. This allows us to avoid the angular scans in our measurements, thus reducing the overall acquisition time while allowing an improvement of statistics.

The work presented in this paper focuses on the Pd/Y based multilayers, which are designed as reflecting mirrors to work in the 7.5-11 nm wavelength range. Derivative systems are also designed with the motivation of improving the optical performance of the reflecting mirror owing to more abrupt interfaces.

Experimental details

Samples are deposited onto sliced and polished Si (100) wafers by using DC magnetron sputtering. The originally designed structure is B4C(2.5 nm)/[Pd(2 nm)/Y(2 nm)]40/Si. The B4C capping layer is added to protect the samples against oxidation. A series of samples is fabricated with 0-6% of nitrogen gas N2 in the sputtering gas instead of pure argon because we believe that the formation of YN will help improve the thermal stability of the sample and reduce the interdiffusion between Pd and Y layers [21,22]. Another series of samples has B4C barrier layers inserted at Pd-on-Y, Y-on-Pd or both interfaces in order to prevent or reduce the interdiffusion between the Pd and Y layers [23]. The thickness of the barrier layers is 1 nm. The physical structures of the samples, including thickness and roughness of each layer are determined by grazing incident X-ray reflectometry immediately following the deposition process.

The proton beam is generated by the Van de Graaff accelerator of the SAFIR (Système d’Analyse par Faisceaux d’Ions Rapides) platform. The proton energy is set at 2.0 MeV, which is suitable to ionize the Pd atoms in their L shell uniformly through the whole multilayer. The energy loss of the proton beam is only about 0.5% after penetrating the multilayer whose total thickness is approximately 200 nm. The X-ray color camera is an iKon-M from Andor Technologies equipped with a 1024×1024 sensor array with 13×13 µm pixels. Instead of using the native spatial resolution, we select a 4×4 binning leading to a resolution of 256×256. Such selection improves the energy resolution by minimizing the charge sharing effect between adjacent pixels while still providing adequate angular resolution. It also simplifies the data treatment by reducing the size of data files. The camera spans an angular range of 2.7° corresponding to 256 horizontal pixels in Fig. 1.

For a given X-ray emission, we measure its intensity as a function of the detection angle with the X-ray color camera while irradiating the sample with the proton beam. The experimental setup is schematically presented in Fig. 1 where the X-ray color camera is placed perpendicular to the incident proton beam with a 200 µm beryllium film to filter the scattered protons. The experimentally obtained image of particle induced X-ray emission (PIXE) presented in Fig. 1 is the spatial distribution of total X-ray intensity on the detected area for B4C(2.5 nm)/[Pd(2 nm)/B4C(2 nm)/Y(2 nm)]40/Si multilayer obtained after a 2 hour irradiation with about 35 nA of 2 MeV protons in a 2 mm beam spot. This
corresponds to about $5 \times 10^{16}$ protons cm$^{-2}$. The Kossel feature cannot be observed on this image yet. It requires further treatment, which will be explained later, to be extracted from this image.

Fig. 1. Geometry of the experimental setup. $\theta$ is the detection angle. The presented experimental image is the spatial distribution of total X-ray intensity on the detector array for B$_4$C(2.5 nm)/[Pd(2 nm)/B$_4$C(2 nm)/Y(2 nm)]$_{40}$/Si multilayer irradiated as described in the text.

Fig. 2. Spectrum of B$_4$C(2.5 nm)/[Pd(2 nm)/B$_4$C(2 nm)/Y(2 nm)]$_{40}$/Si multilayer: a) overview, intensity in log scale; b) zoomed range of interest, intensity in linear scale.

Note that a complete X-ray spectrum is recorded by each pixel of the X-ray color camera. To identify the emission peaks, we sum the spectra recorded by all pixels in order to get more reliable statistics. An overview (intensity in log scale) of the summed X-ray spectrum of the B$_4$C(2.5 nm)/[Pd(2 nm)/B$_4$C(2 nm)/Y(2 nm)]$_{40}$/Si sample as well as the zoomed range of interest (intensity in linear scale) are presented in Fig. 2. The Y K$\alpha$ emission can be observed on the spectrum at photon energy near 15 keV, but due to its low intensity and small estimated angular range for Kossel detection (about 0.5° grazing exit angle, in the total reflection zone), it would not be possible to observe its Kossel oscillation. The energy calibration of the spectrum is carried out with Pd L$\alpha$ (2.838 keV) and Y K$\alpha$ (14.958 keV) peaks. Y L$\alpha$ and Si K$\alpha$ emissions are not considered because their energies are close to the low energy limit of the camera and their detection is not as efficient as Pd L$\alpha$ emission. Pd L$\beta$ emission is not discussed either because its intensity is much less than that of the of Pd L$\alpha$ emission and would not
bring supplementary information. The Pd Lα1 and Lα2 emissions are not resolved, the difference in their energies being less than the detector resolution of about 150 eV at Mn Kα (5.9 keV). A region of interest (ROI) is placed on the spectrum in order to distinguish the Pd Lα emission from other photons, see Fig. 3(a) where the intensity of Pd Lα emission is obtained by integrating the shadowed area. The ROI width of 100 eV is based on a compromise between obtaining good statistics and limiting the influence of the Pd Lβ emission. An image of the spatial distribution of the Pd Lα emission intensity (Fig. 3(b)) is obtained after applying the energy filtering ROI of Fig. 3(a) to the total intensity image presented in Fig. 1. While it is not possible to observe the Kossel feature in Fig. 1, now it can be clearly seen in Fig. 3(b). Finally we integrate this filtered image along the vertical pixels in order to obtain the Kossel curve which is presented in Fig 3(c).

![Fig. 3.](image)

**Fig. 3.** a) Selection of the ROI for Pd Lα emission; for the case already depicted in Fig. 1: b) image of the intensity of X-ray emission, of which the energy is in the ROI; c) Kossel curve depicted by integrating the X-ray emission intensity along the vertical pixel.

To check the stability of the measurement and possible sample damage from the proton irradiation, we consider the sample B₄C(2.5 nm)/[Pd(2 nm)/B₄C(2 nm)/Y(2 nm)]₄0/Si and continue measuring for over 7 hours. The result is presented in Fig. 4 where the curve intensities are normalized by the proton beam current and the acquisition time. We divide this series of measurements into 4-time slices and depict separately the related Kossel curves of Pd Lα emission to see if any deformation of the Kossel feature happens. The oscillation maintains its shape, indicating that the structure of the multilayer is not changed during the measurement and the proton beam causes no discernible change to the sample structure. We can safely say that the whole experiment is non-damaging because the standard acquisition time for each sample is about 2 hours.
Fig. 4. Non-damaging test of the sample B₄C(2.5 nm)/[Pd(2 nm)/B₄C(2 nm)/Y(2 nm)]×40/Si.

The relation between the grazing exit angle and the channel in pixel of the detector is determined with the angular variation of Pd Lα emission intensity of the 4-layer sample B₄C(2.5 nm)/[B₄C(1 nm)/Pd(2 nm)/B₄C(1 nm)/Y(2 nm)]×20/Si where both the first and second orders of the Kossel diffraction can be observed. The calibration method, which is based on the comparison between experimental and simulated Kossel curves, is presented in Fig. 5. The experimental data and its derivative enable us to locate the position of the Kossel oscillation in pixels, which together with the angle of the Kossel oscillation from simulated curve gives 1° equals to 94.42 channel. Thus the angular range of the X-ray color camera is $256/94.42 = 2.71°$. The simulation method will be presented later.

Fig. 5. Calibration of the detection angle using the comparison between a) experimental and b) simulated Kossel curves.

Results and discussion

In Fig. 6 we present the Kossel curves for Pd Lα emission of all measured samples. To facilitate the comparison of the shapes of the curves, for each sample the origin of the detection angle is set to
the Bragg angle, which corresponds to the center of its Kossel oscillation. Fig. 6(a) shows the Kossel curves of the Pd/Y multilayers deposited with a proportion of N₂ within the argon sputtering gas ranging from 0 to 6%. For the Pd/Y multilayer grown in pure argon we observe no Kossel feature at all. This indicates that the intermixing is so severe that even the periodicity of the multilayer is compromised. As the proportion of N₂ increases, we start to observe the Kossel feature and its contrast (defined as the difference between the maximal and minimal intensity values as the detection angle crosses the Bragg angle) increases as well. As expected [21,22], the nitrogen has a positive effect in preventing or reducing the intermixing at the interfaces of the multilayer. Fig. 6(b) presents the Kossel curves of the multilayers with 1 nm B₄C diffusion barriers at one given interface or at both interfaces. The Kossel feature of each sample can be clearly observed. For the two samples with 1 nm B₄C barrier layer inserted at either Y-on-Pd or Pd-on-Y interfaces (noted as B₄C/Pd/Y 122 and Pd/B₄C/Y 212 respectively), the Kossel features are different when the detection angle is higher than the Bragg angle. The first one exhibits an intensity maximum at +0.05° while the latter shows rather flattened feature at the same angular position. When inserting 1 nm B₄C at both interfaces (the sample labeled as B₄C/Pd/B₄C/Y 1212), the intensity maximum at +0.05° become even more obvious, however at -0.05° the intensity decrease of the curve is more flattened than the two samples mentioned above. Here we do not present the sample mentioned in the previous section with 2 nm B₄C barrier layer because it is considered expendable for the long-time non-damaging test. Thus it is unsuitable to be put in the comparison series.

Fig. 6. Kossel curves for Pd Lα emission of all measured samples. a) series of samples fabricated with different concentration of N₂ in the sputtering gas; b) series of samples with B₄C barrier layers at one given interface or at both interfaces. For this latter series, the name of the samples refers both to the order of the layers within the period and to the thickness (in nm) of the individual layers.

To simulate the PIXE-Kossel curve, we build model of the multilayer using the structural parameters (thickness and roughness of the layers) determined by grazing incident X-ray reflectivity. The simulation method is originally designed for X-ray fluorescence calculation under Kossel effect [2]. It calculates the electric field generated by the emitted X-ray within the multilayer under X-ray irradiation. We make an approach in order to adapt it to the PIXE-Kossel calculation. Since the ionization is uniform through the whole multilayer, we consider the incident proton beam as an photon beam with neither attenuation nor refraction. Such approach actually simplifies the calculation. An example of the simulation is given in Fig. 7 where both experimental and simulated the PIXE-Kossel
curves are presented in the near Bragg angle zone. The agreement is fairly good showing that the PIXE-Kossel curve can be used to determine the structure of multilayer stack.

Fig. 7. Comparison between experimental result and simulation of the PIXE-Kossel curves of the sample B$_4$C(2.5 nm)/[B$_4$C(1 nm)/Pd(2 nm)/B$_4$C(1 nm)/Y(2 nm)]$_{20}$/Si.

**Conclusion**

We have shown the feasibility of using proton induced X-ray emission combined with Kossel diffraction to characterize the structure of nanometric multilayers. We have measured the Kossel diffraction of proton induced Pd L$_\alpha$ emission in Pd/Y based multilayers. Compared to our previous experiment [20], we have significantly improved the data acquisition with the X-ray color camera. We also demonstrate here that the shape of the Kossel curve is very sensitive to the detailed structure of the multilayer and its interface. In particular we confirm that nitridation during the multilayer deposition process has a positive effect in preventing or reducing the interdiffusion between Pd and Y layers, and we further show that Pd/Y based multilayers with B$_4$C barrier layers at different interfaces can be distinguished by the shape of their Kossel curves.

**References**


